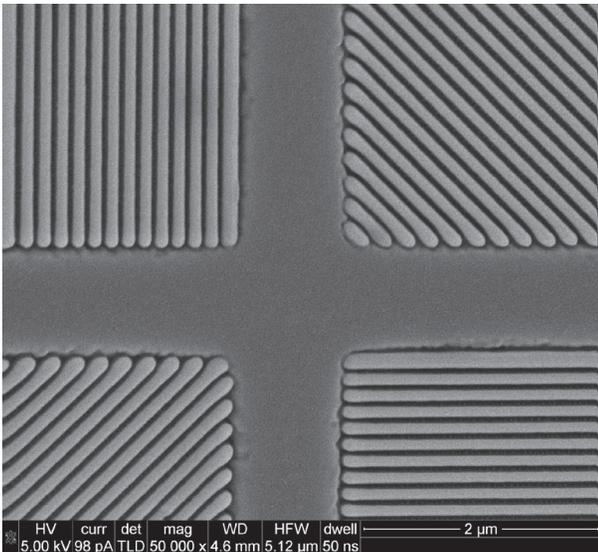
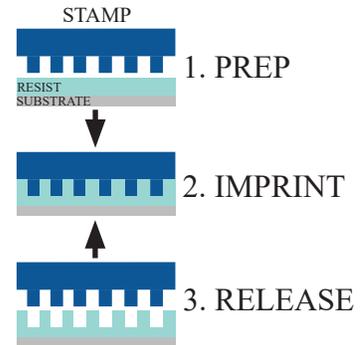
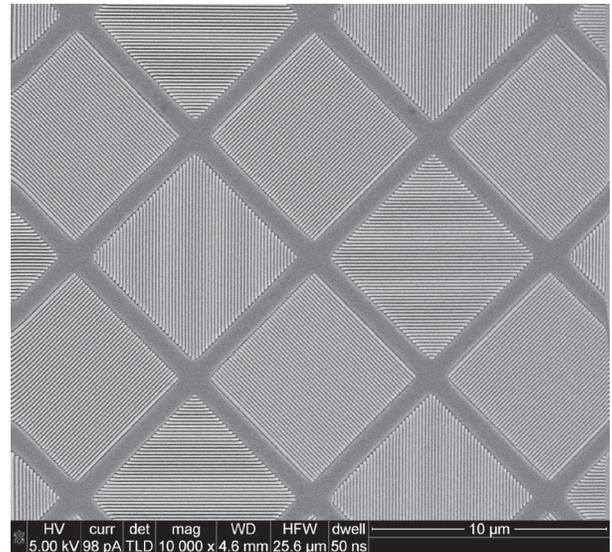


Nanoimprint Lithography and Fabrication all Inclusive Service

MOXTEK has developed 8-inch nanoimprint processes to manufacture subwavelength 3-D nanostructures. We offer imprinting, etching, and fabrication capabilities for your product needs on glass-like wafers and have successfully tested silicon, display glass, and sapphire as substrate materials. We also demonstrated the capability to imprint a 4-state pixelated aluminum wire-grid polarizer with 7µm pixel pitch and 144nm wire pitch as shown in the images below. Thus far, Moxtek has imprinted feature sizes less than 30nm wide and less than 50nm tall.



captions



captions

General Specifications

Substrate Materials	Display glass, N-BK7, Borofloat, Fused Silica, Silicon, Sapphire, or any type of glass-like materials
Nanostructure Materials	Dielectrics and metals
Feature Size	< 30nm width, < 50nm height
Wafer Size	8 inch (200mm)
Products	Metasurfaces, Waveguides, Wire Grid Polarizers, Diffractive Optics and other subwavelength nanostructures